

Application No. 10/660,687

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*AMENDMENTS TO THE CLAIMS*

This listing of claims replaces all prior versions, and listings, of claims in the application.

1. (Currently Amended) A chemical-mechanical polishing composition system for planarizing or polishing a composite substrate comprising (i) ~~a polishing composition comprising~~ (a) about 0.5 wt.% to about 10 wt.% of a source of fluoride ions, (b) about 1 wt.% to about 10 wt.% of an amine, (c) about 0.1 wt.% ~~or more~~ 0.5 wt.% to about 8 wt.% of a base, and (d) ~~water, and~~ (ii) about 0.1 wt.% to about 30 wt.% of an abrasive, and (e) water.
2. (Currently Amended) The composition system of claim 1, wherein the composition system has a pH of about 7-14.
3. (Currently Amended) The composition system of claim 1, wherein the abrasive is selected from the group consisting of alumina, silica, titania, ceria, zirconia, germania, magnesia, coformed products thereof, and mixtures thereof.
4. (Currently Amended) The composition system of claim 3, wherein the abrasive is silica.
5. (Canceled)
6. (Canceled)
7. (Currently Amended) The composition system of claim 1, wherein the fluoride ions are from a source of fluoride ions selected from the group consisting of fluoride salts, fluoride acids, fluoride metal complexes, and combinations thereof.
8. (Currently Amended) The composition system of claim 1, wherein the amine is an amino alcohol.
9. (Currently Amended) The composition system of claim 8, wherein the amine is 2-dimethylamino-2-methyl-1-propanol.
10. (Currently Amended) The composition system of claim 1, wherein the base is selected from the group consisting of inorganic hydroxide bases and carbonate bases.

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11. (Currently Amended) The composition system of claim 10, wherein the base is selected from the group consisting of potassium hydroxide, sodium hydroxide, ammonium hydroxide, cesium hydroxide, sodium carbonate, and mixtures thereof.

12. (Currently Amended) The composition system of claim 1, wherein the composition system further comprises a quaternary ammonium compound.

13. (Currently Amended) The composition system of claim 1, wherein the composition system has a polishing selectivity of oxide:nitride of about 2:1 or more.

14. (Currently Amended) The composition system of claim 1, wherein the composition system comprises a cationic species that reduces nitride removal from the composite substrate.

15. (Currently Amended) The composition system of claim 1, wherein the fluoride ions comprise less than about 100% active fluoride ions.

16. (Currently Amended) The composition system of claim 1, wherein the composition system has a free alkalinity value of about 0.001-0.15 mol/l.

17. (Currently Amended) The composition system of claim 1, wherein the composition system has a total alkalinity value of about 0.005-0.2 mol/l.

18-42. (Canceled)